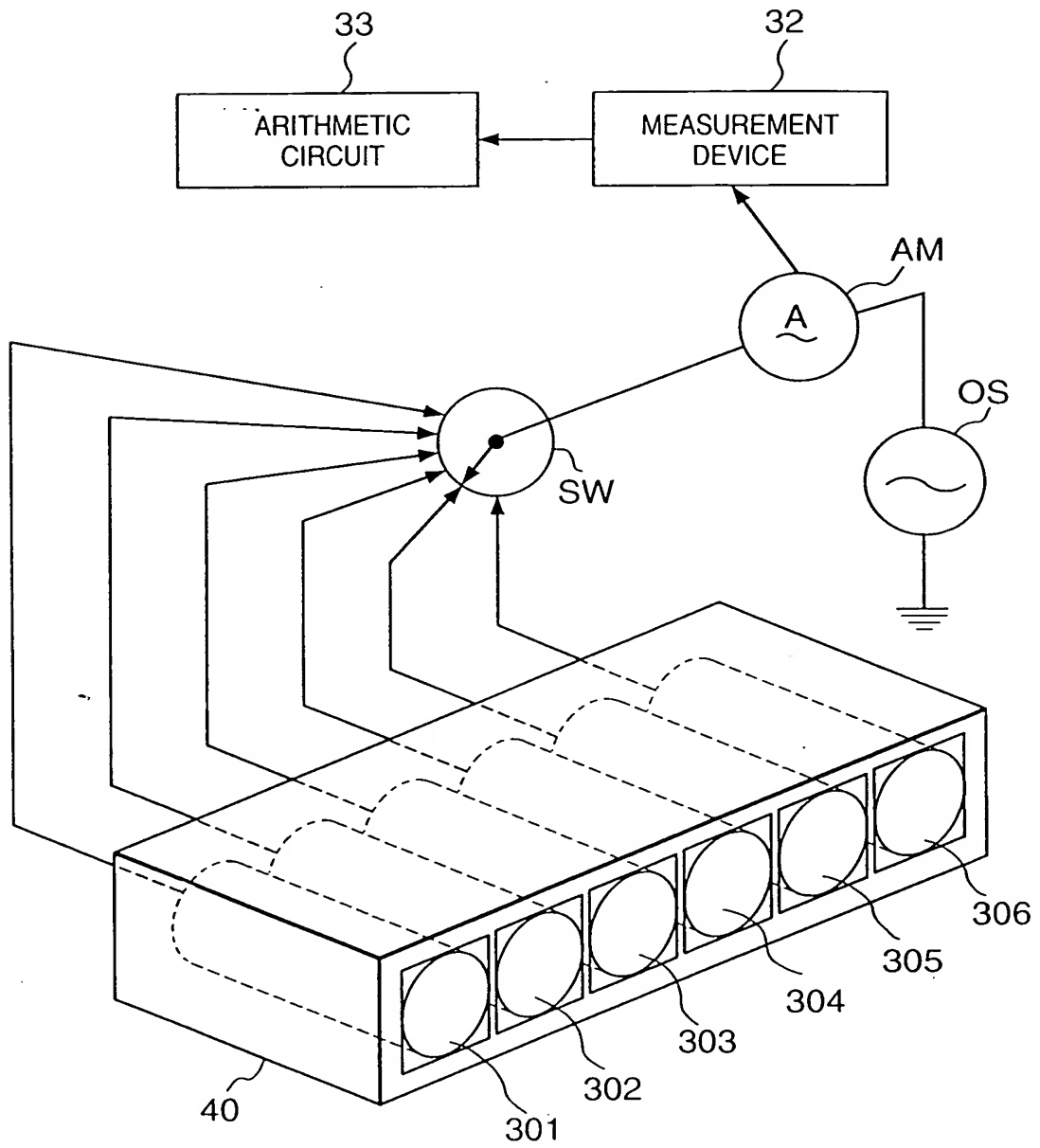


FIG. 1



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FIG. 3

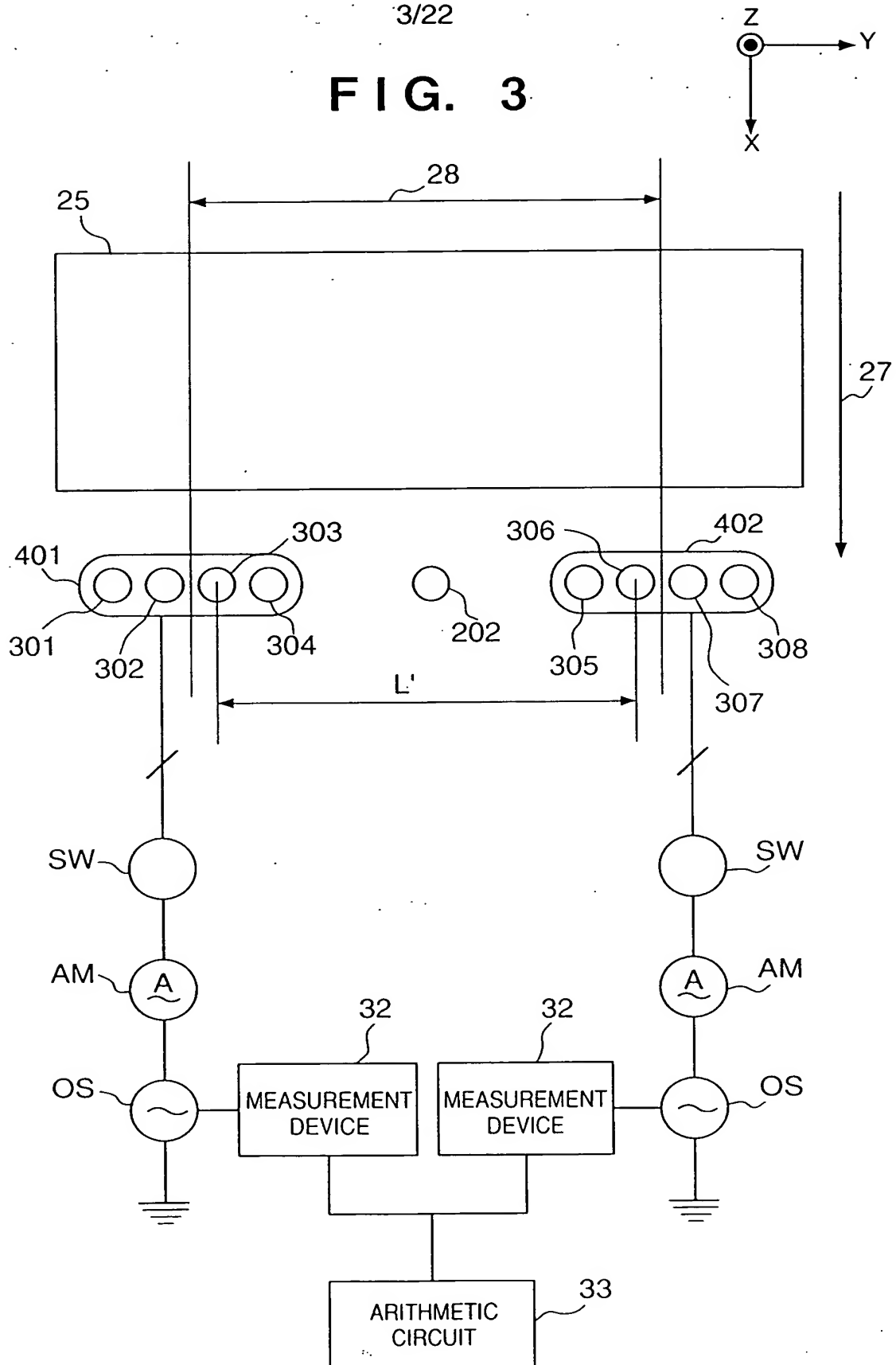


FIG. 4

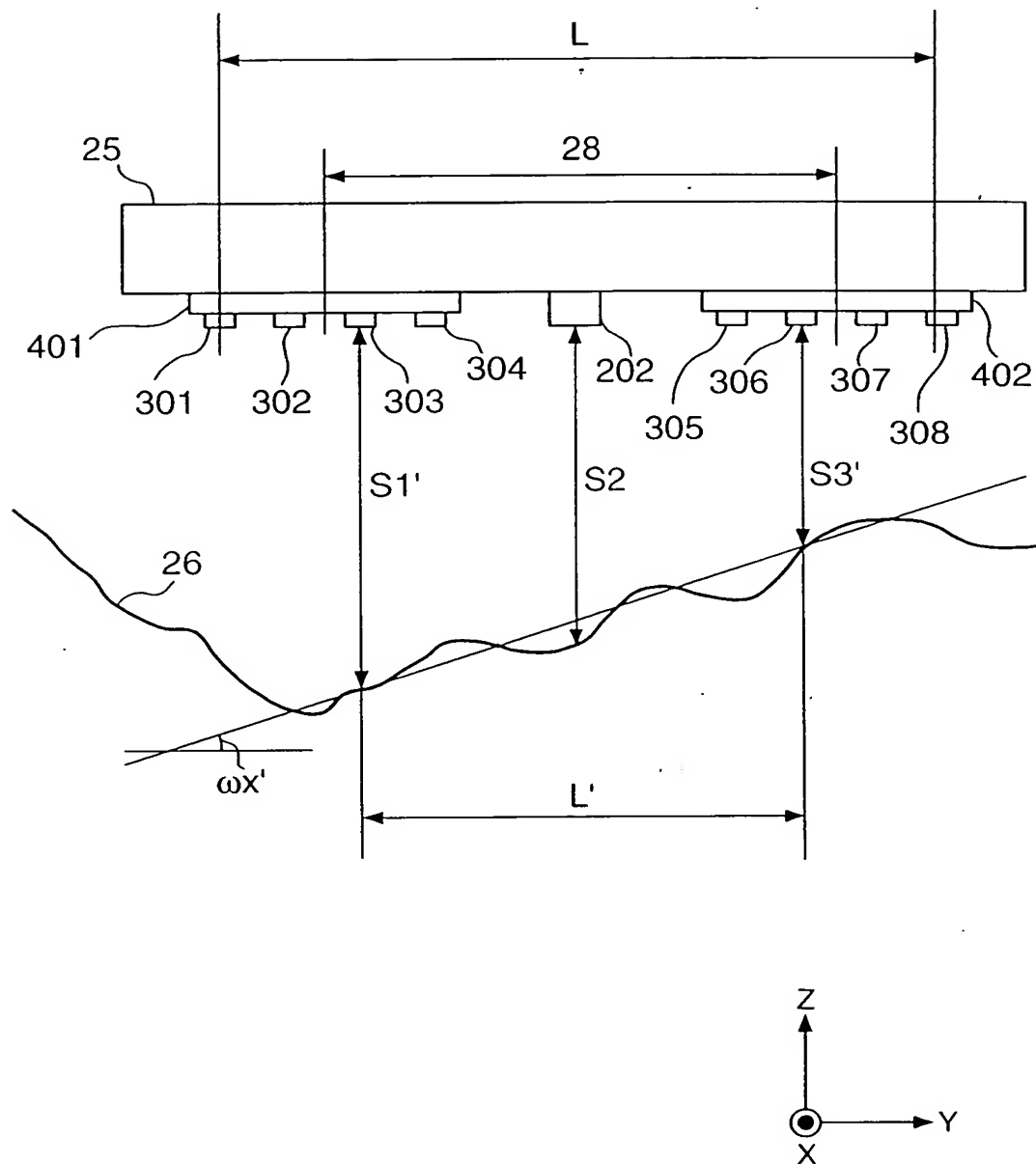
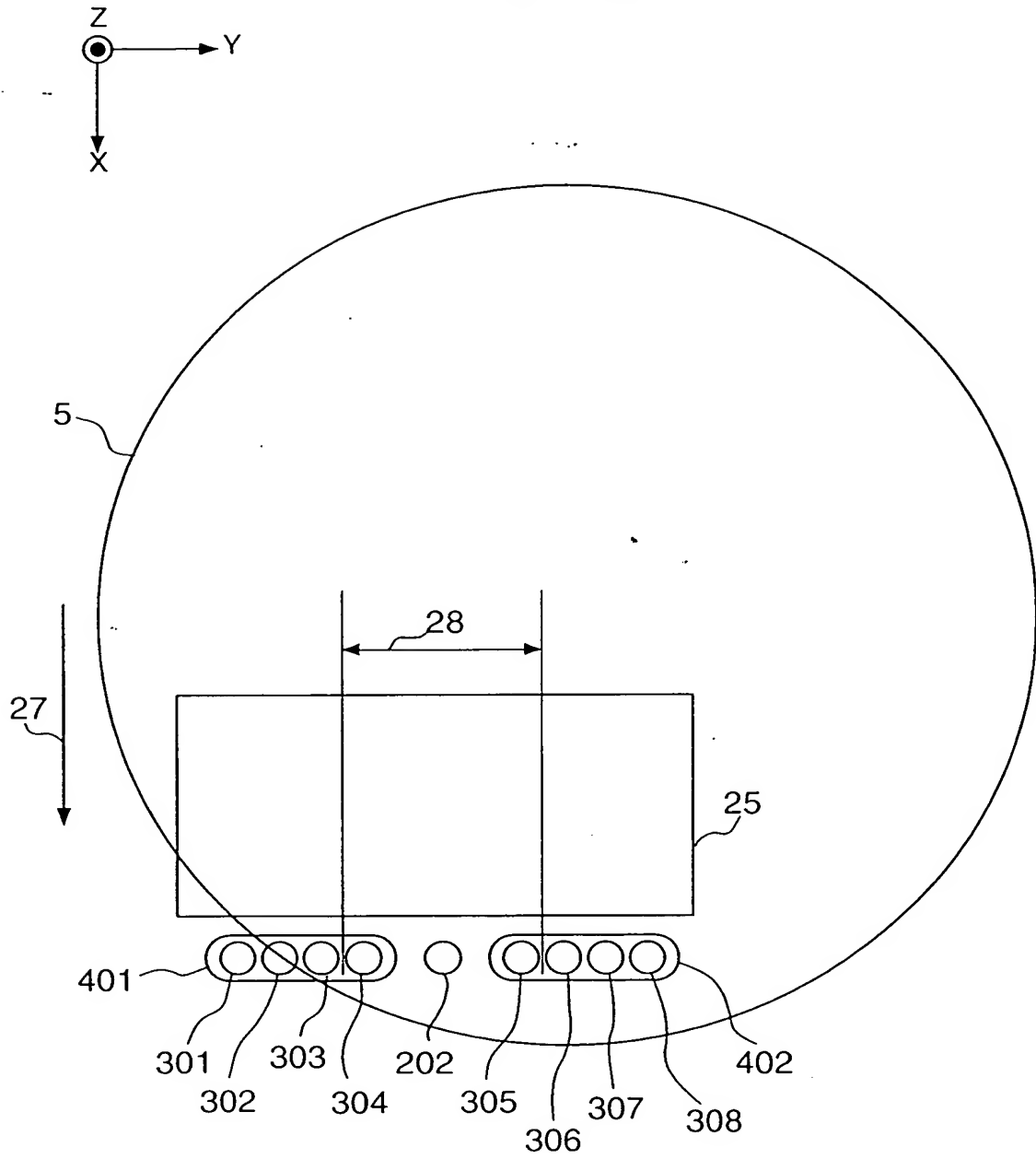


FIG. 5



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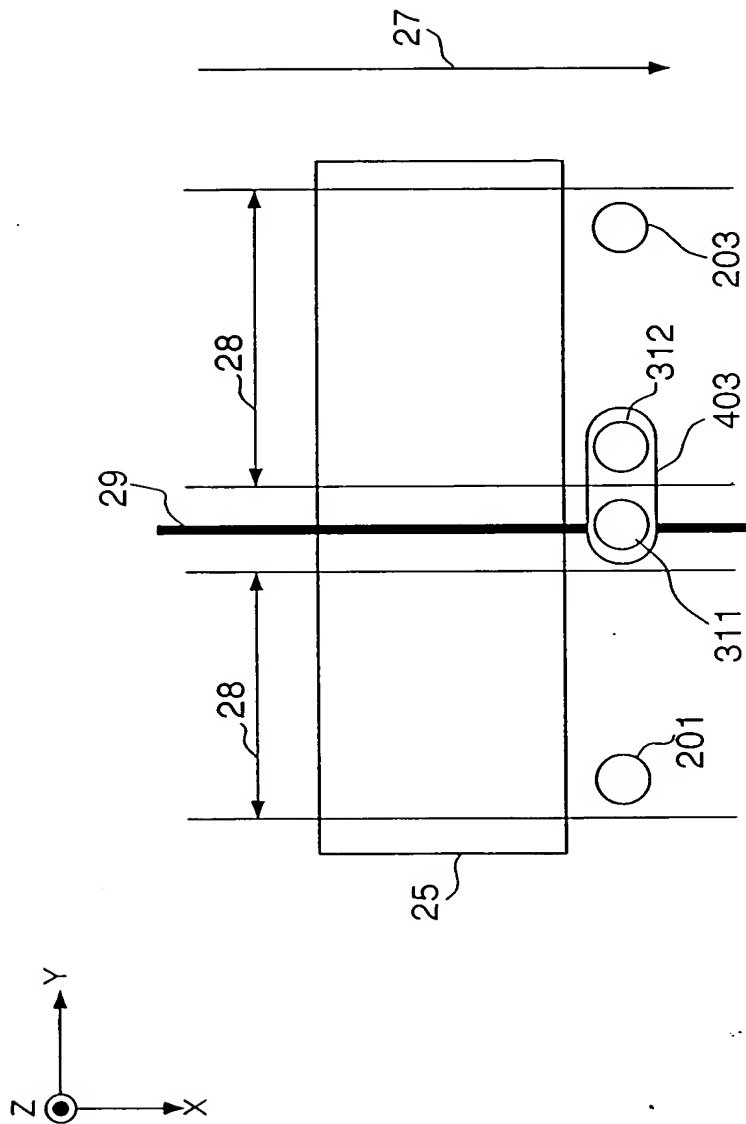


FIG. 7

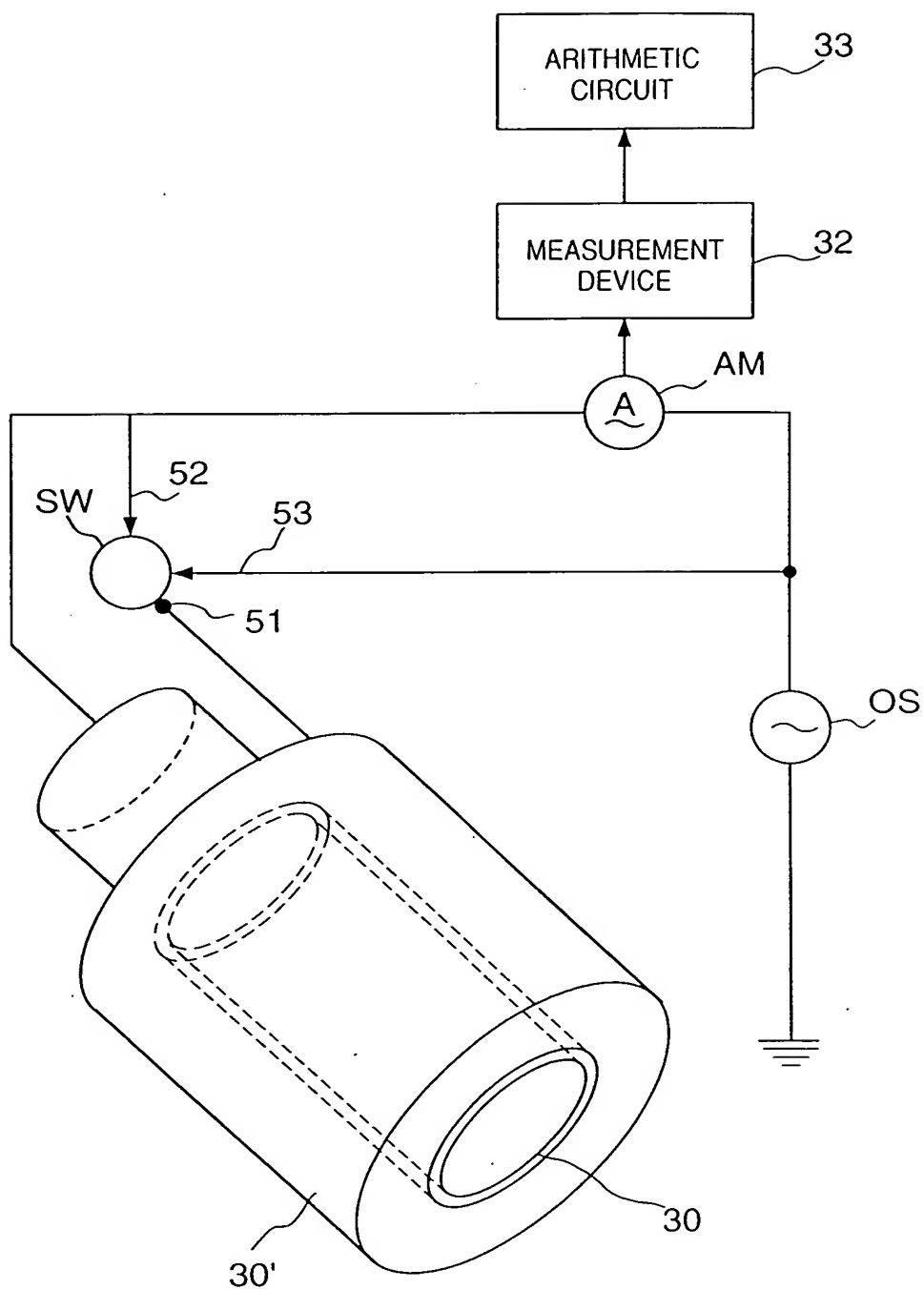
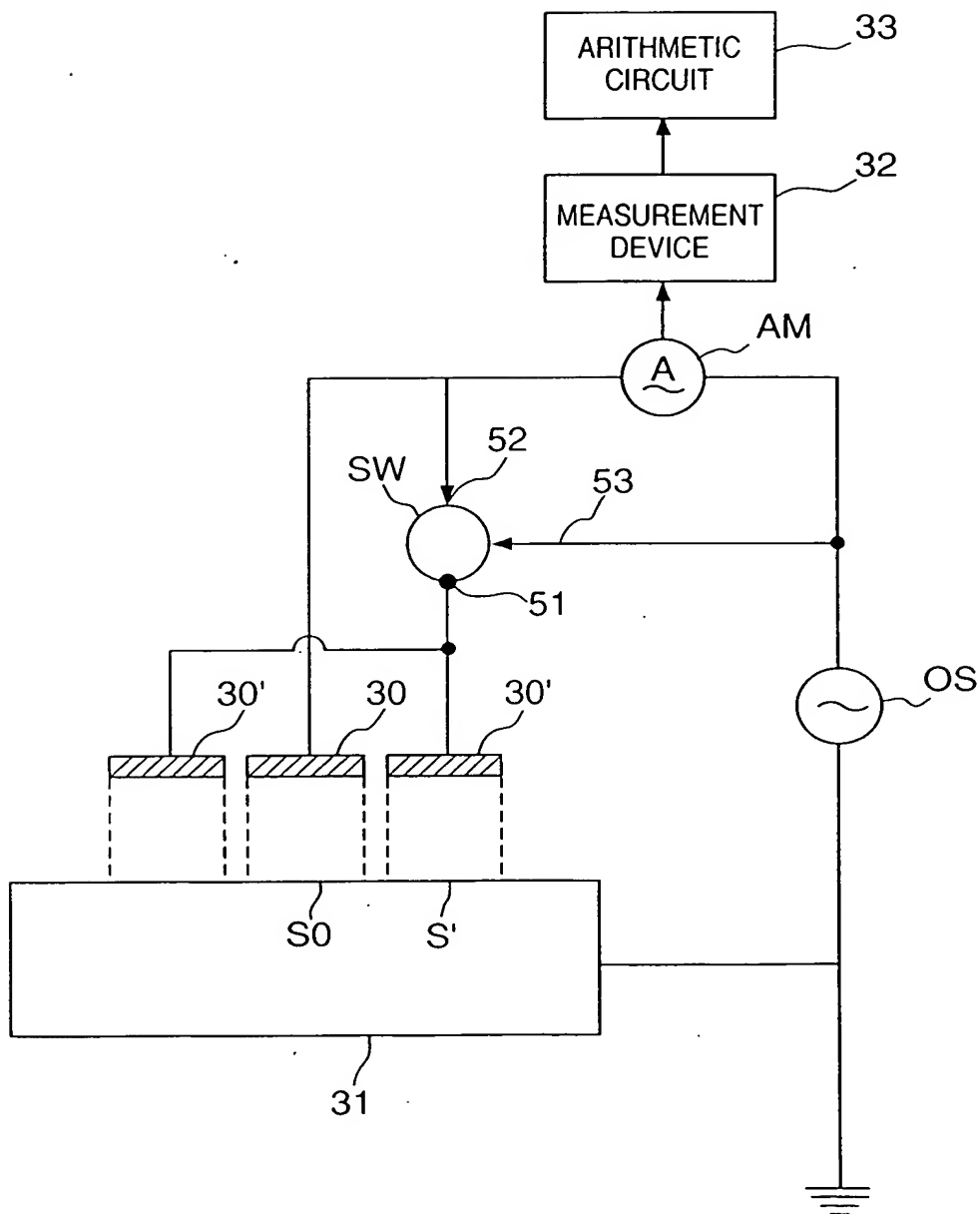


FIG. 8



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FIG. 9

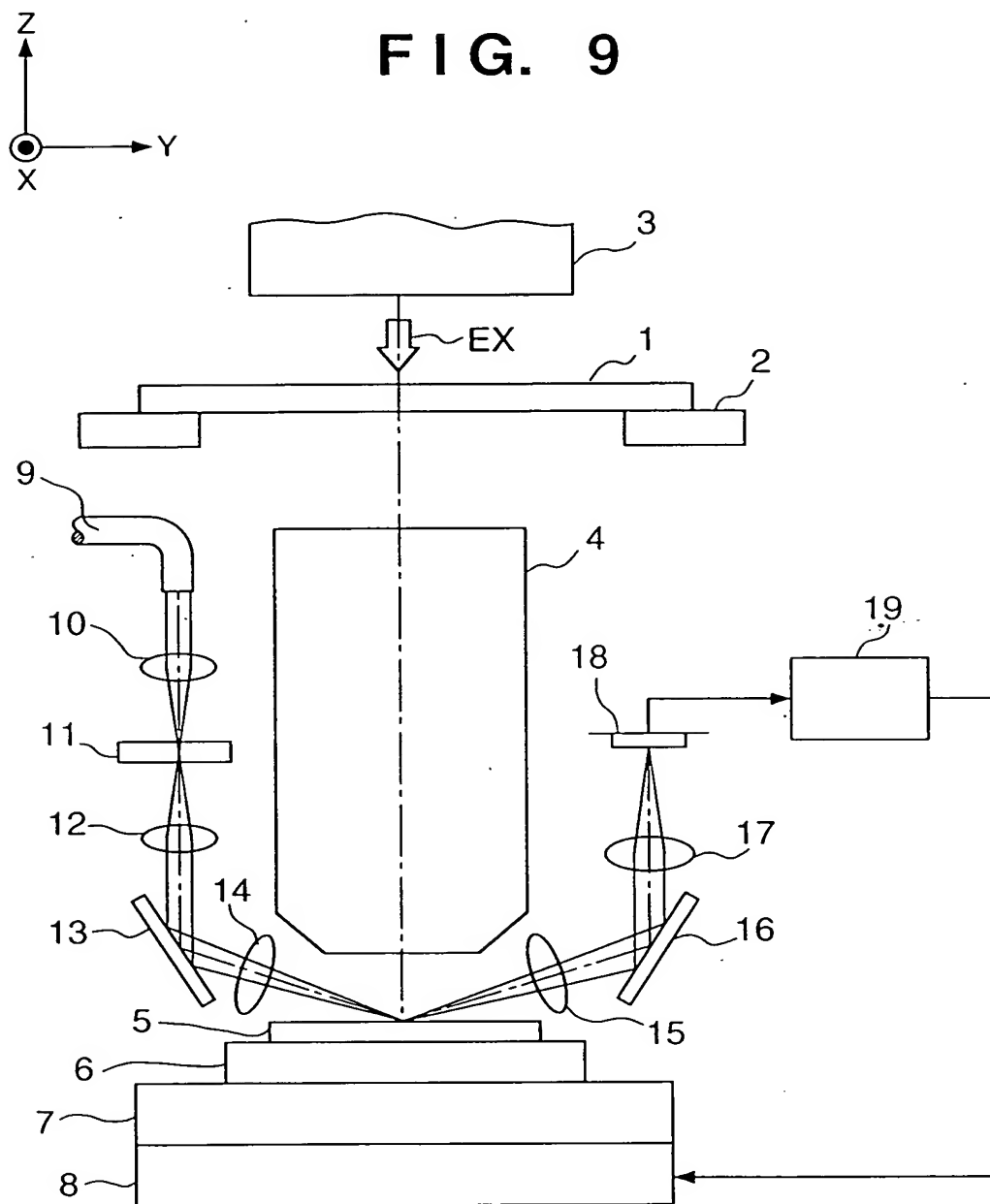
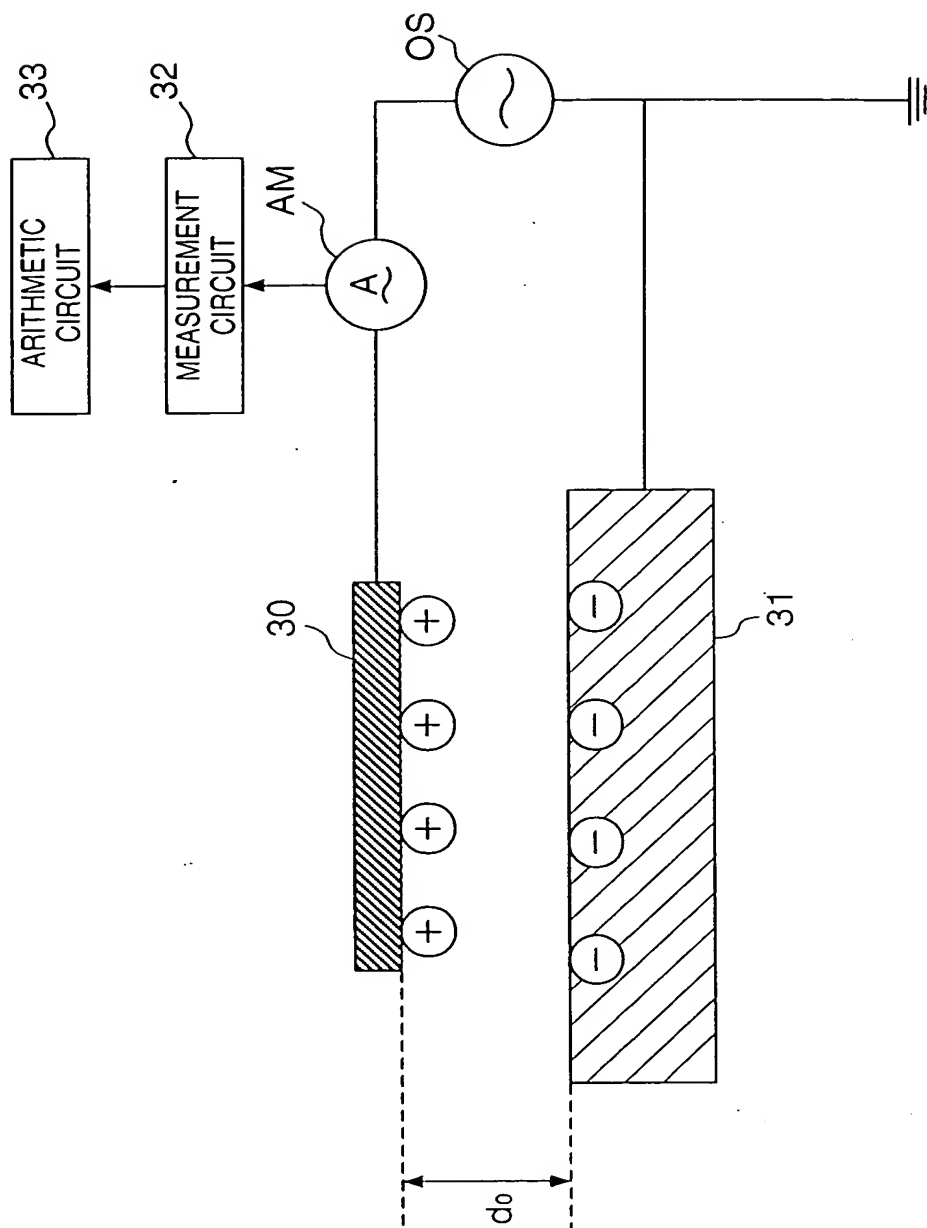


FIG. 10



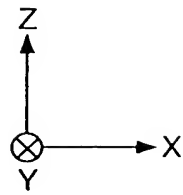
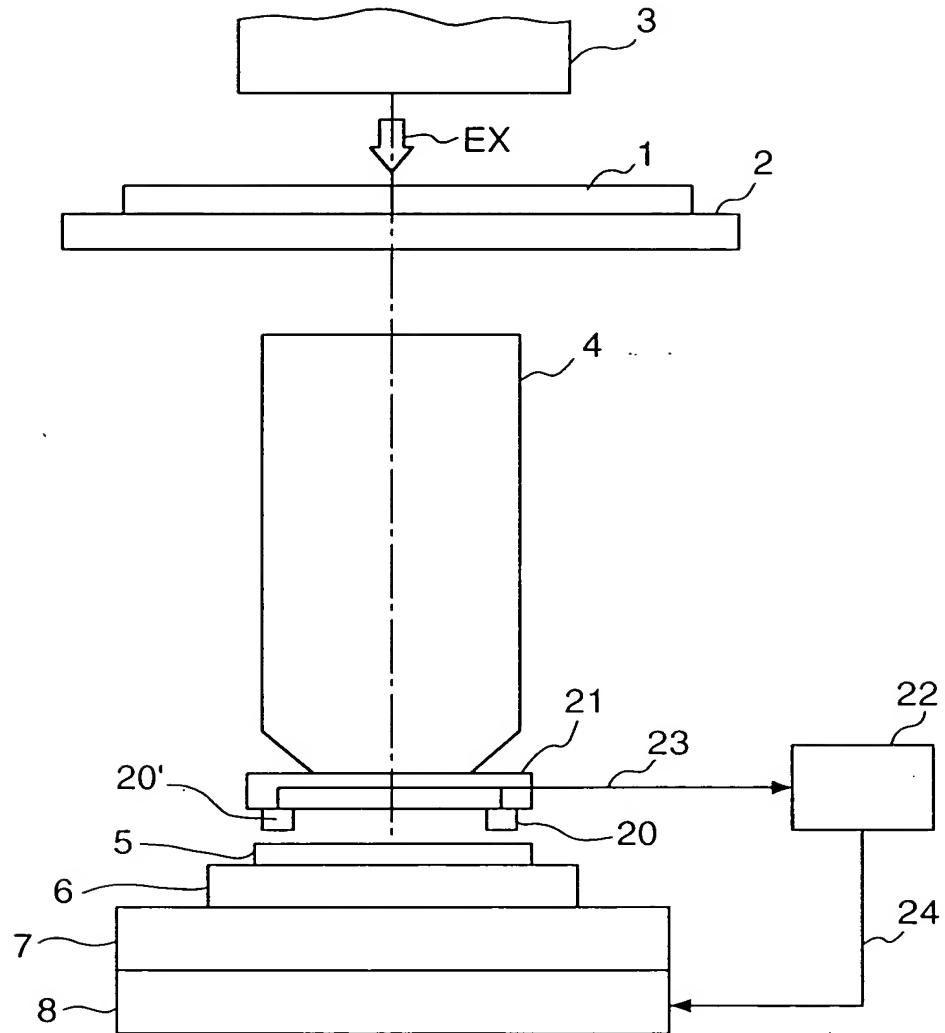


FIG. 11



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FIG. 12

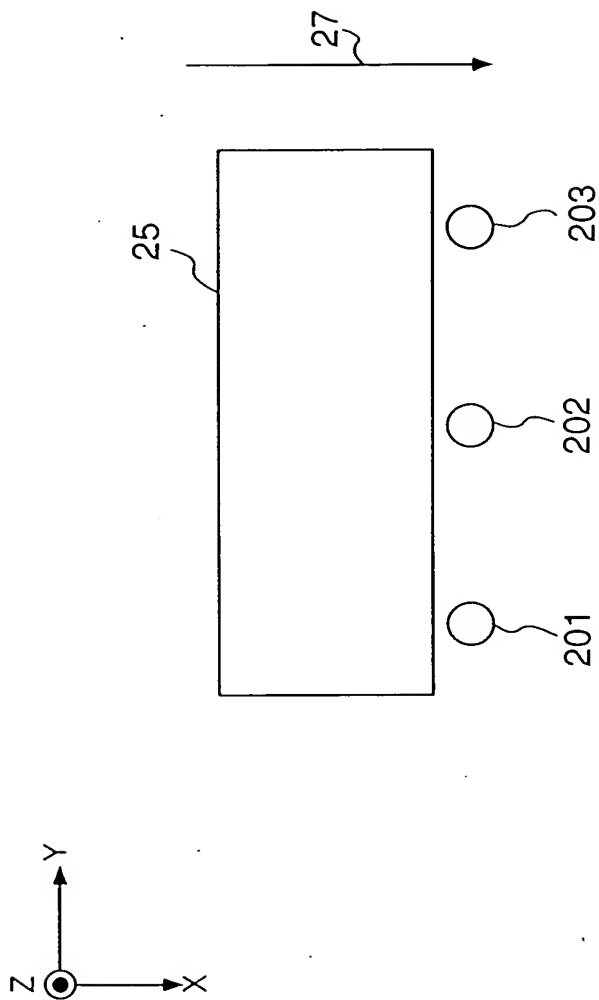
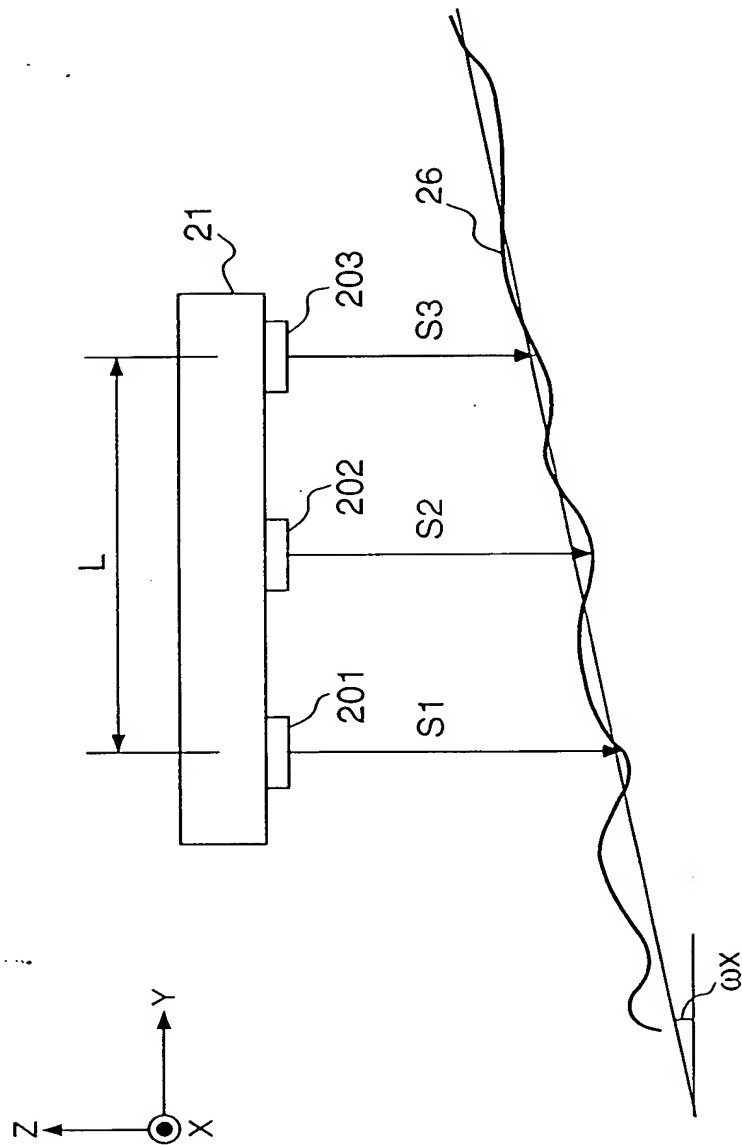


FIG. 13



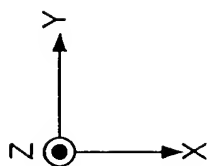


FIG. 14

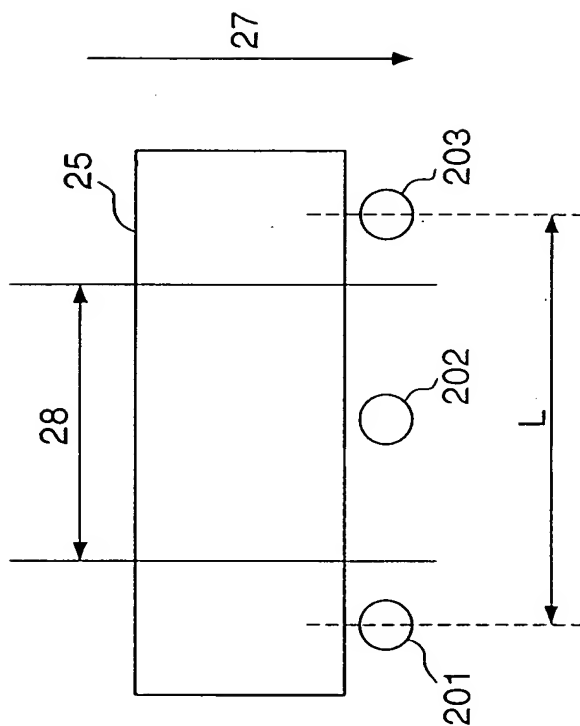


FIG. 15

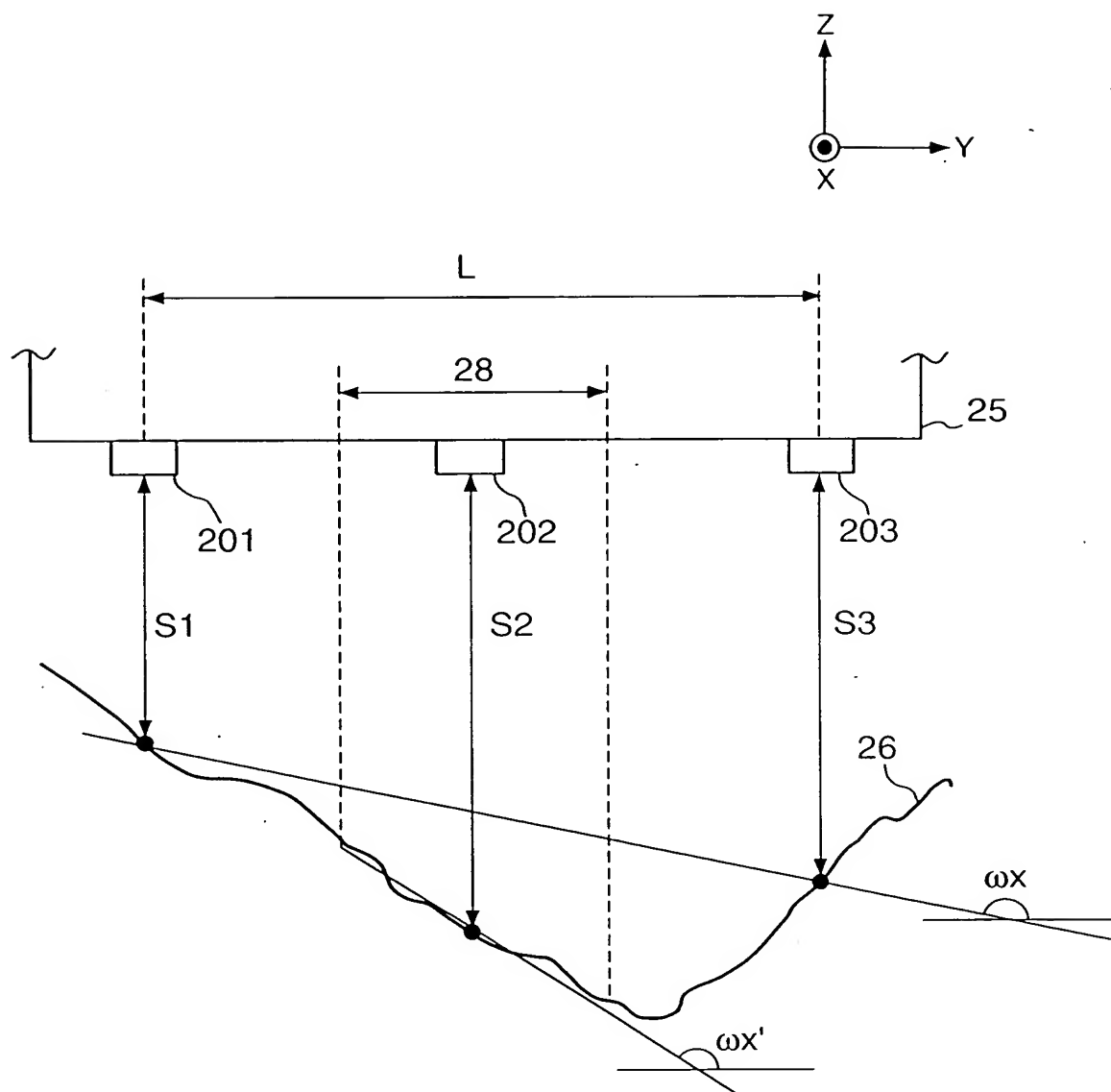


FIG. 16

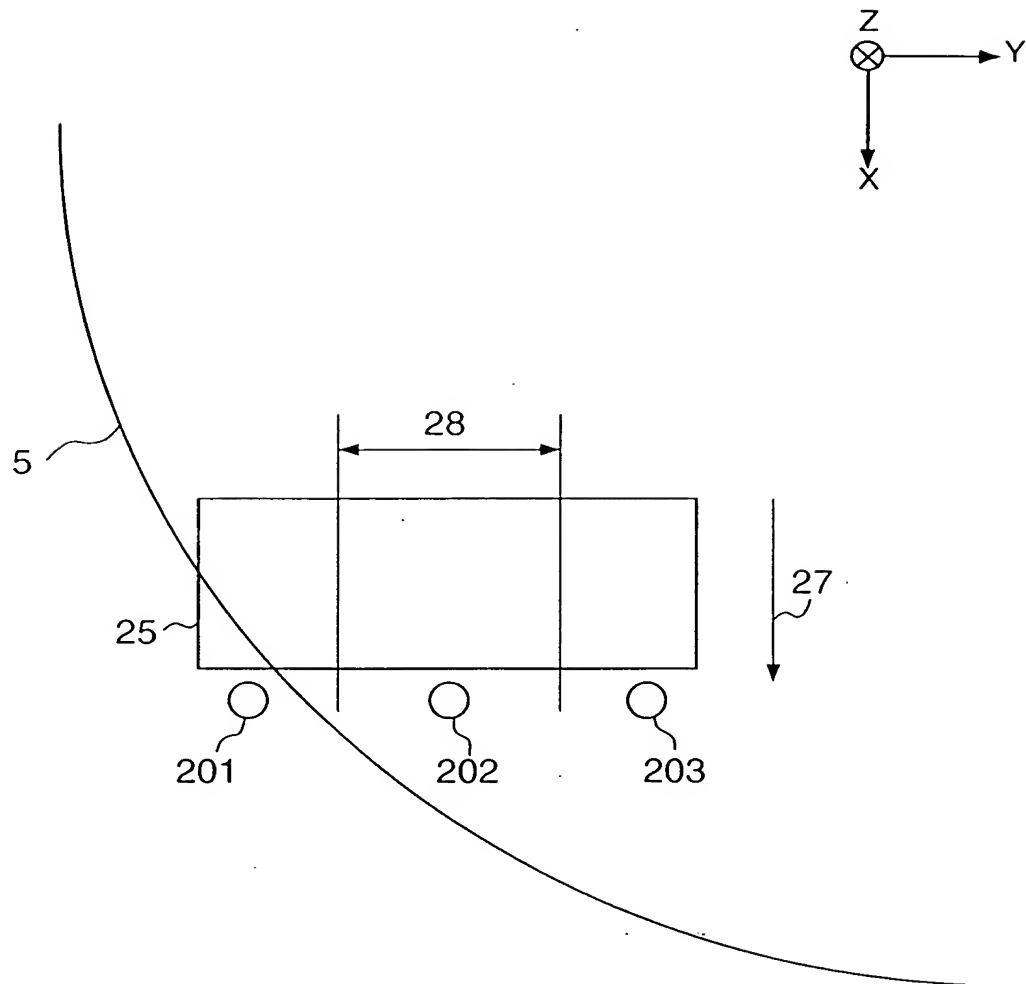
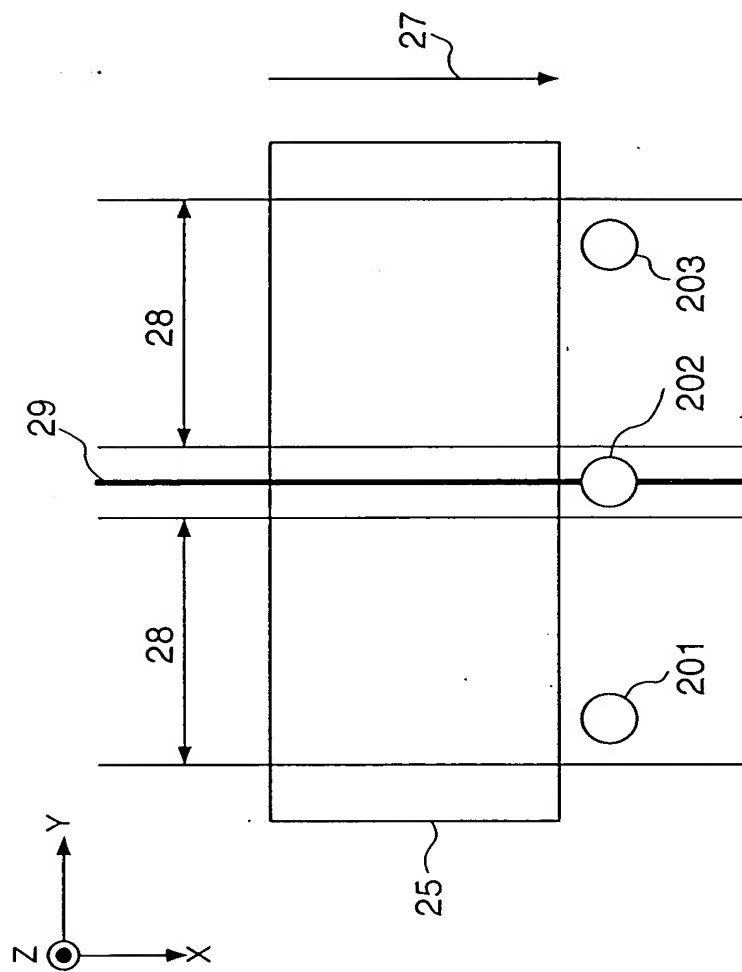




FIG. 17



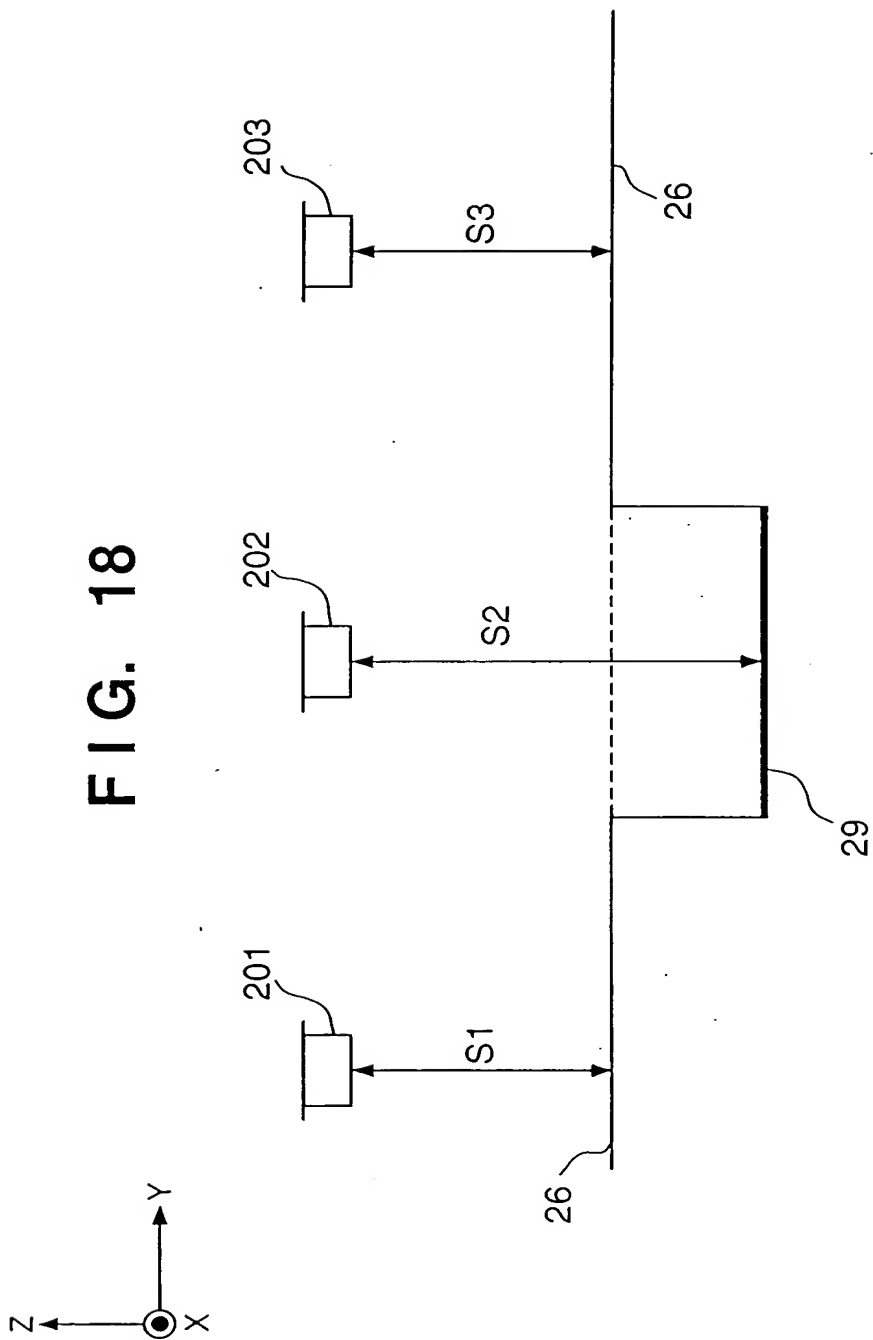
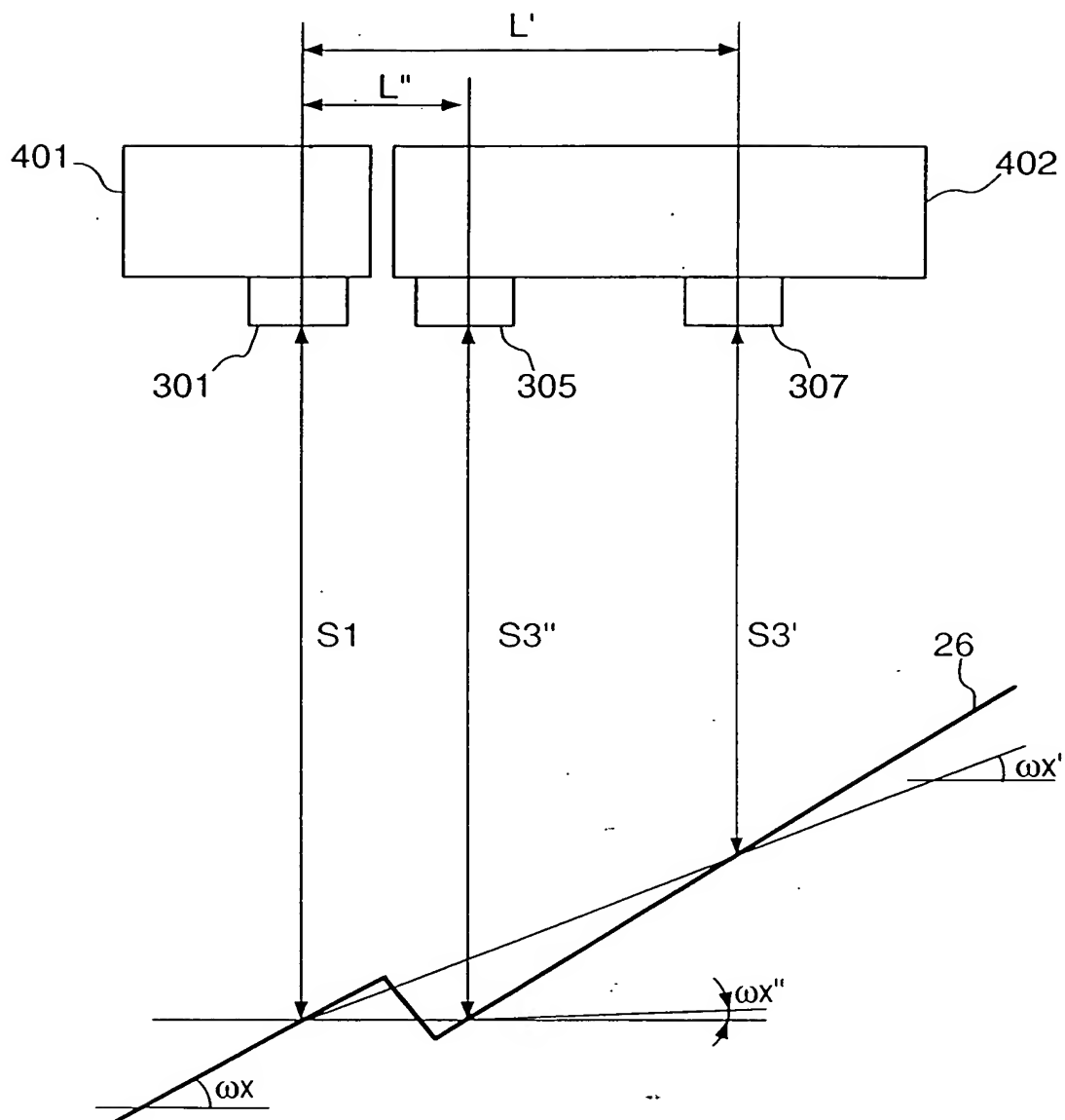


FIG. 19



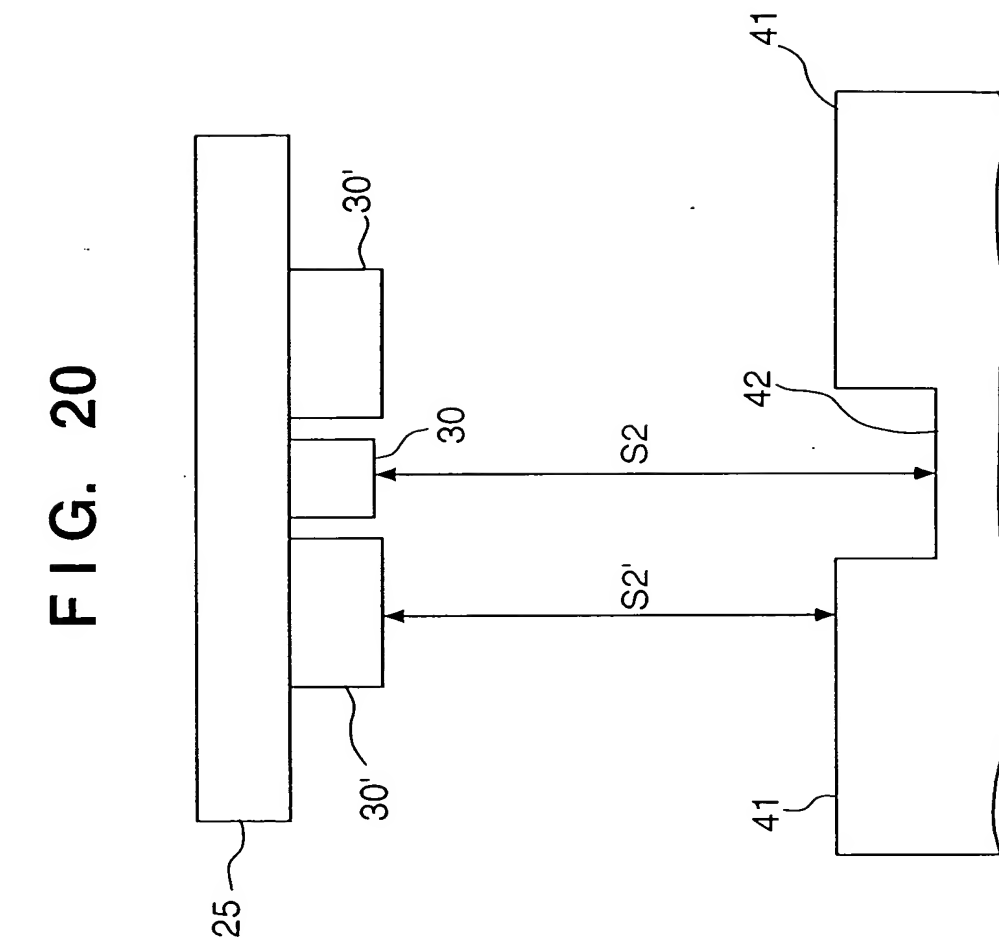
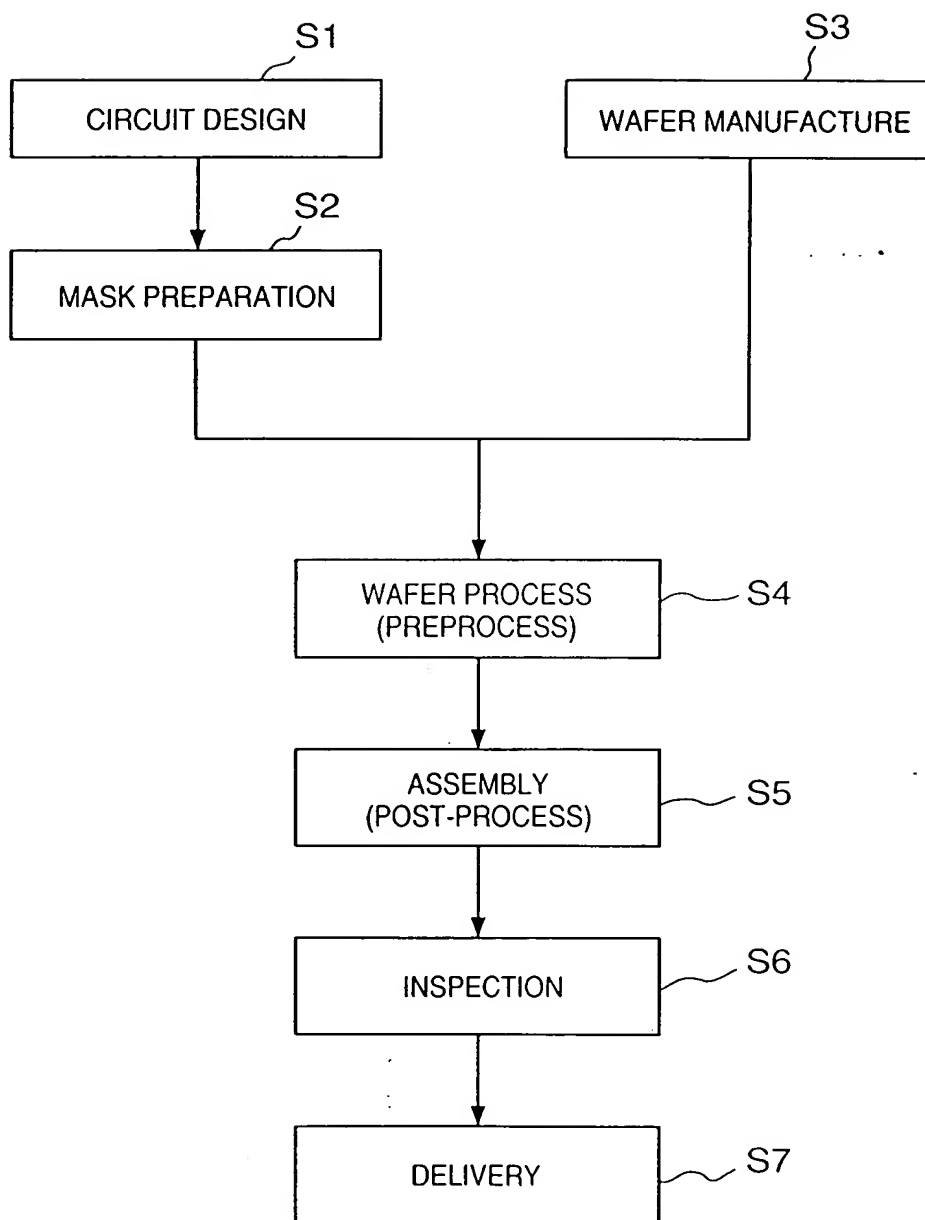


FIG. 21



SEMICONDUCTOR DEIVCE MANUFACTURING FLOW

